

Amendments to the Specification:

Please amend the abstract of the disclosure as follows:

The main object of the present invention is to provide a method for manufacturing an EL element is disclosed which can manufacture the EL element efficiently even in a case where patterning of a hole injecting layer is difficult and the hole injecting layer is needed to be formed on the entire surface of a substrate. To attain the above mentioned object, the present invention provides a A method for manufacturing an electroluminescent element includes comprising at least: a hole injecting layer forming process of forming a hole injecting layer on a first electrode layer formed side surface of a base material with the first electrode layer formed ~~on the surface~~ in a pattern; a decomposition removing process of using a photocatalyst treatment layer substrate having at least a photocatalyst treatment layer containing a photocatalyst formed on a substrate, placing the base material with the hole injecting layer formed thereon and the photocatalyst treatment layer substrate facing each other with a gap of 200 µm or less ~~so that the photocatalyst treatment layer substrate and the hole injecting layer are facing to each other~~, decomposing and removing the hole injecting layer ~~in between the first electrode layers~~, in a pattern, on the base material ~~with the hole injecting layer formed thereon~~ by irradiating with energy from predetermined direction; a light emitting layer forming process of forming a the light emitting layer on the pattern formed hole injecting layer remaining on the base material; and a second electrode layer forming process of forming a the second electrode layer on the light emitting layer; wherein a contact angle to a liquid of the surface of the hole injecting layer is smaller than the contact angle to a liquid of the surface bared by removing the hole injecting layer ~~in the decomposition removing process~~.